

Single step route to highly transparent, conductive and hazy aluminium doped zinc oxide films

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Supplementary information:

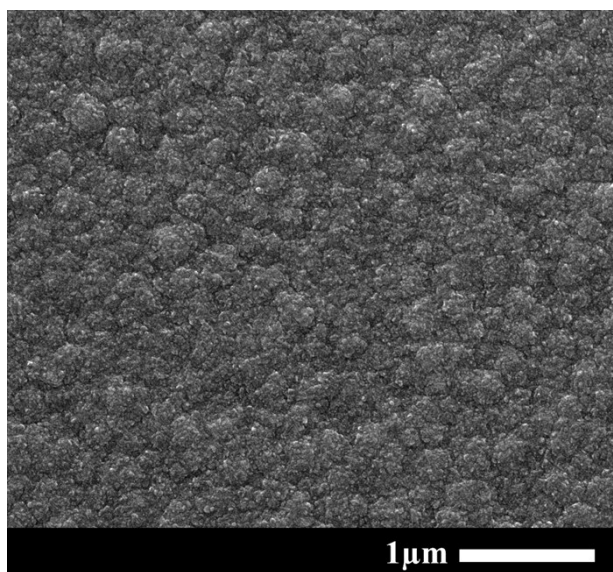


Figure S1: SEM image of as-prepared undoped ZnO thin film by AACVD under 500 °C without using acetylacetonate as additive in the precursor.

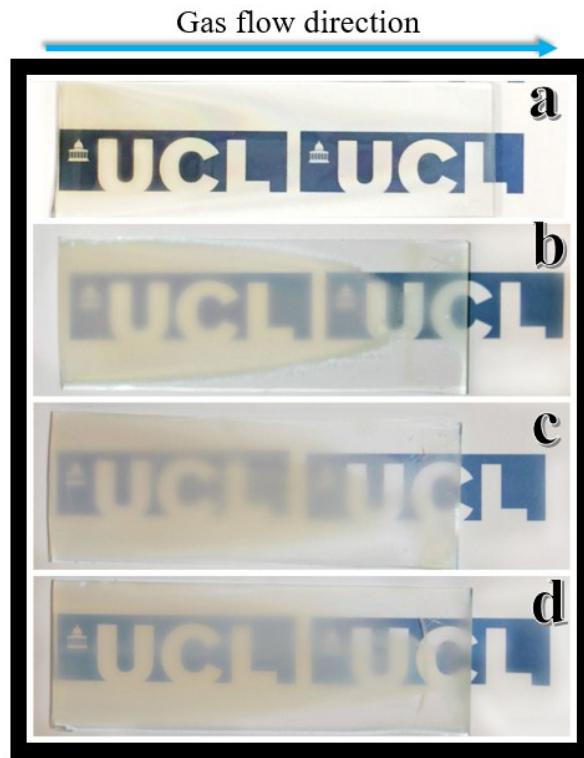


Figure S2: Digital photo showing the appearance of all as-prepared ZnO thin films : a) non-additive undoped ZnO film, b) additive treated undoped ZnO film, c) additive treated 2.9 at.% Al doped ZnO film and d) additive treated 6.1 at.% Al doped ZnO film.

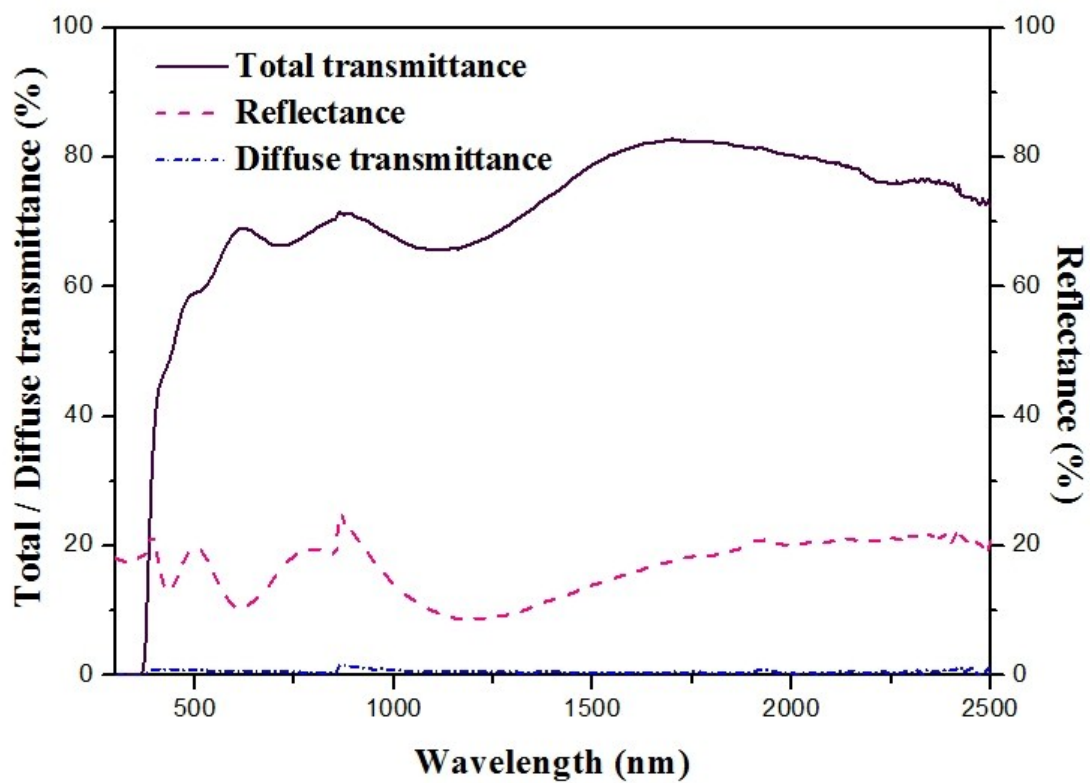


Figure S3: Optical properties of non-additive undoped ZnO film: Total transmittance, reflectance and diffuse transmittance.